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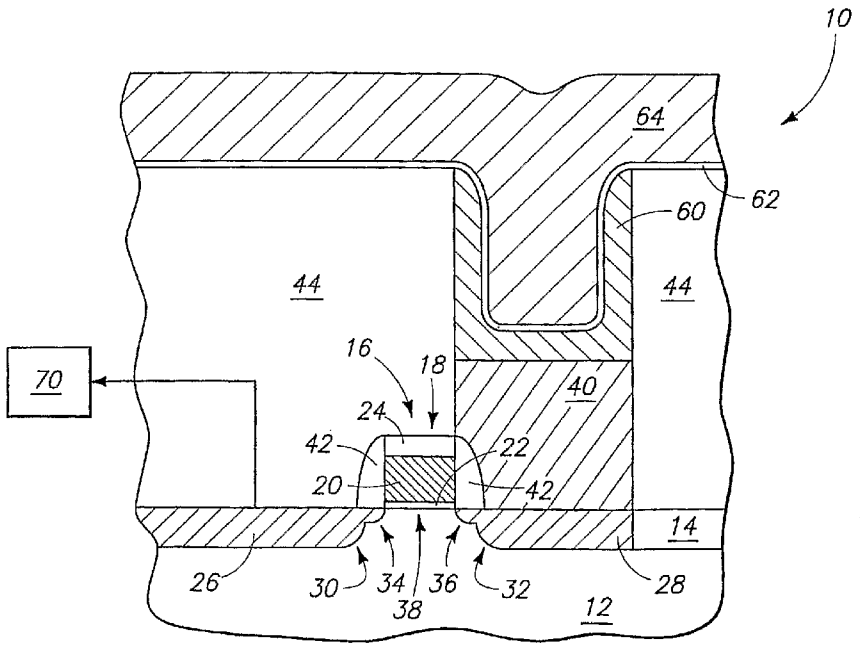
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(54) Title: METHODS OF ETCHING OXIDE, REDUCING ROUGHNESS, AND FORMING CAPACITOR CONSTRUCTIONS



(57) Abstract: The invention includes methods in which one or more components of a carboxylic acid having an aqueous acidic dissociation constant of at least 1×10^{-6} are utilized during the etch of oxide (such as silicon dioxide or doped silicon dioxide). Two or more carboxylic acids can be utilized. Exemplary carboxylic acids include trichloroacetic acid, maleic acid, and citric acid.

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